Title: Patterning with Rigid Organic Under-Layer Inventor(s): Christopher Lyons et al. Case No.: 03-05 (H2004), Sheet 1/5

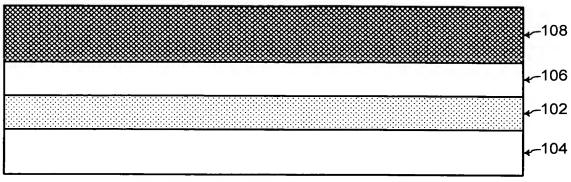


FIG. 1 (Prior Art)

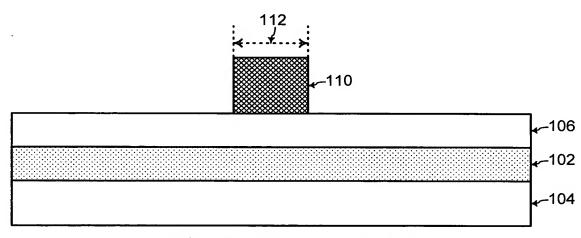


FIG. 2 (Prior Art)

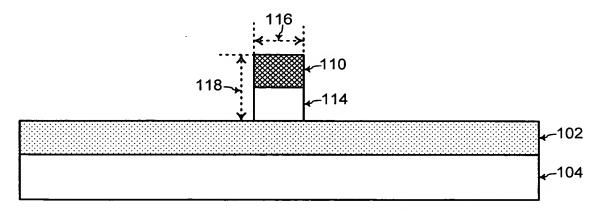


FIG. 3 (Prior Art)

<u>2000</u> Unit(s) for Etching Mask Structure(s) Photolithography Unit 242 **Deposition Unit Photoresist** 218 214 Rigid Organic Under-Layer **Deposition Unit** Unit for Etching IC Material 210 Solution for Photoresist Development FIG. 4 220 238 **Deposition Unit** Hard-mask 206 Unit for Etching Hard-mask Layer Rigid Organic Under-Layer Unit for Etching 226 234 204

Title: Patterning with Rigid Organic Under-Layer Inventor(s): Christopher Lyons et al. Case No.: 03-05 (H2004), Sheet 2/5

Title: Patterning with Rigid Organic Under-Layer Inventor(s): Christopher Lyons et al. Case No.: 03-05 (H2004), Sheet 3/5

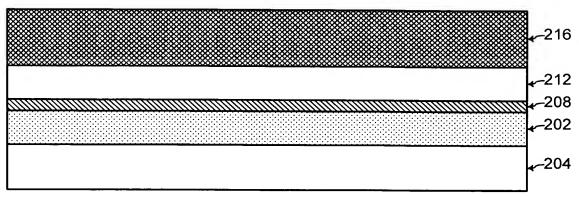


FIG. 5

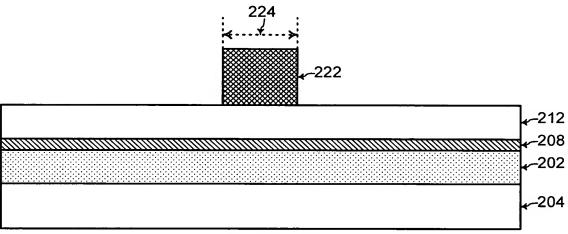


FIG. 6

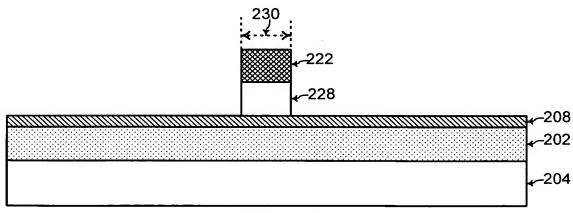
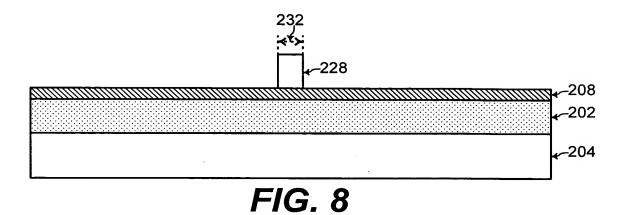
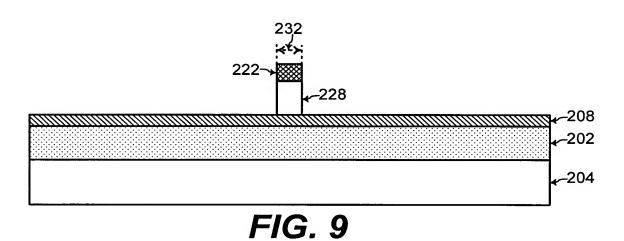
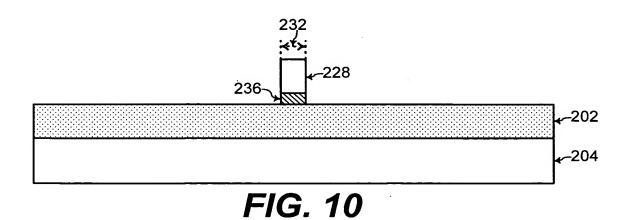


FIG. 7

Title: Patterning with Rigid Organic Under-Layer Inventor(s): Christopher Lyons et al. Case No.: 03-05 (H2004), Sheet 4/5







Title: Patterning with Rigid Organic Under-Layer Inventor(s): Christopher Lyons et al. Case No.: 03-05 (H2004), Sheet 5/5

